



5/2/02
#17/Response

Patent
Attorney's Docket No. 027260-295

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of)

Kazuya KAMON)

Application No.: 09/320,946)

Filed: May 26, 1999)

For: PHOTOMASK, FABRICATION)
METHOD OF PHOTOMASK, AND)
FABRICATION METHOD OF)
SEMICONDUCTOR INTEGRATED)
CIRCUIT)

Group Art Unit: 1756

Examiner: S. Mohamedulla

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TC 1700

RESPONSE UNDER 37 C.F.R. §1.116

Assistant Commissioner for Patents
Washington, D.C. 20231

Date: May 3, 2002

Sir:

This response responds to the Office Action dated January 3, 2002 (Paper No. 16).
Concurrently attached to this response is a Petition for Extension of Time for one month
extension and copies of three references.

REMARKS

This response responds to the Office Action dated January 3, 2002 in which the
Examiner rejected claims 7-8 and 22-23 under 35 U.S.C. § 112, first paragraph, rejected
claims 7, 22, 23 and 28 under 35 U.S.C. § 102(b), rejected claims 2, 5, 7, 9-11, 14, 15,
17-23 and 28 under 35 U.S.C. § 102(e) and rejected claims 1-6, 8-21, 24 and 27 under 35
U.S.C. § 103.

Applicant respectfully traverses the Examiner's rejection of claims 7-8 and 22-23
under 35 U.S.C. § 112, first paragraph. Applicant respectfully points out to the Examiner,